

Figure 1A

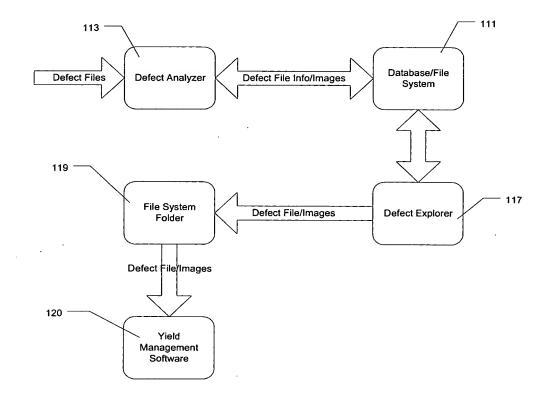
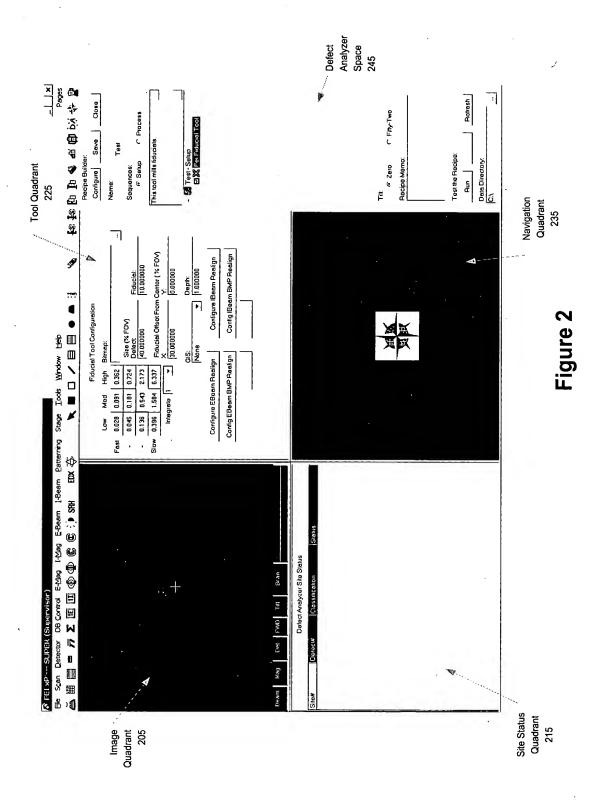


Figure 1B



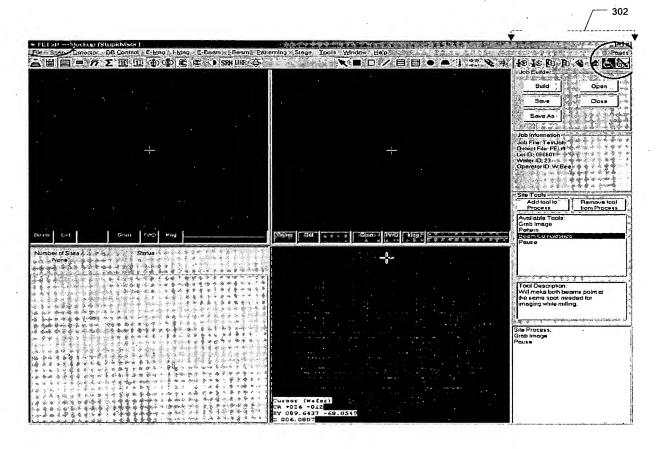


Figure 3A

ltem	Description
Job Builder:	·
Build	Initiates building of new job
Save .	Save the job information.
Save As	Functions conventionally
Open	Functions conventionally
Clase	Functions conventionally
Job Information	Functions conventionally
Site Tools:	
Add Tool to Process	Inserts selected tool into process
Remove Tool from Process	removes selected tool from process
Available Tools	Displays tools available for processes
Tool Description	Brief description of tool
Site Process	Displays process (recipe) as it is being constructed by user

Figure 3B

	etteletetetetetete
Available Tools:	- 4
Grab Image	100
Pattern	10
Beom Coincidence	
Pause	
	<b>A</b>
	- 5
3 I	
Tool Description:	1.
Will make both beams point at	4
the same spot needed for	
imaging while milling.	
	1 1
2 T 1 T 1 T 1 T 1 T 1 T 1 T 1 T 1 T 1 T	
Site Process:	
Site Process: Grab Image Pause	
Grab Image	The control of the co
Grab Image	The state of the s
Grab Image	The state of the s
Grab Image	

Figure 3C

Job wa	fer Data Ir	put	1.10	BF9-146*	<b>23:32</b> :
8 H 1	Job V	Wafer I	Data I	Input	
	Operator II				
	DefectFile	7	rn, J. sylung, rur-turthyem		
	Lot(ID)	060265			
	Job File:	Teswob			
	Product.	Train Ali	15354 74		
		Wafer when	and the same of th	nplete	
	Run		C	ancel	

Figure 3D

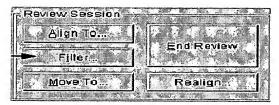


Figure 3E

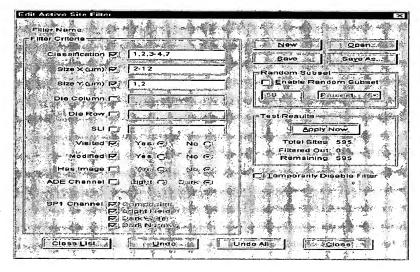


Figure 3F

Interface Items	Description
Filter Name	Identifies the filter.
Filter Criteria	These check boxes and list boxes select the filter criteria.
New	Creates a new filter file.
Open	Opens an existing filter.
Save	Saves the edited filter definition. It is available only if allowed by configuration.
Save As	Saves the edited filter definition to a new file name. It is available only if allowed by configuration.
Random Subset	Specifies the maximum number of random sites passing the filter.
Test Results	Tests and reports the effect of site filter changes.
Temporarily Disable Filter	Temporarily disables the active site filter.
Graph	Displays a histogram of the defect sites.
Class List	Opens the Edit Class List dialog box.
Undo	Undoes the last change. You cannot undo changes already saved to file.
Undo Ail+	Undoes all changes made since dialog box opened. You cannot undo changes already saved to file.
Close	Closes the dialog box. Applies the defined filter to the current review session but does not save the filter to file.

Figure 3G

Criterion	Value Type	Description
Classification	Integer	Classification code assigned to the site
Size X (µm)	Real ·	X dimension of the site in microns
Size Y (µm)	Rea1	Y dimension of the site in microns
Die Colum+n	Integer	Die column of the die containing the site
Die Row	Integer	Die row of the die containing the site
SLI	Integer	Scattered light intensity reported for the site
Visite d	Yes/No	Site has or has not been visited during the review session
Modified		Site has or has not been classified or relocated during the review session
ADE Channel	Light/Dark	Select sites from either the light or the dark channel.
SP1 Channel	n/a	Site has selected attributes. This filter is active if the defect format is T7x00 and the defect file has more than one channel.
Has Image	Yes/No	Site has or does not have image data associated with it

Figure 3H

Relational Operators	Meaning
=	Equal to
· !=	Not equal to
<	Less than
<=	Less than or equal to
>	Greater than
>=	Greater than or equal to

Figure 3I

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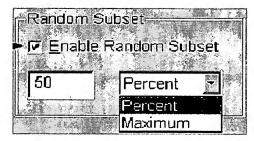


Figure 3J

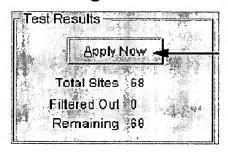


Figure 3K

fei2.001
@05
K54148350
814FC

Figure 3L

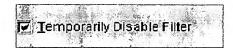


Figure 3M

Defect#	Size X	Size Y	Classification Recipe Name	Die Row

Figure 3N

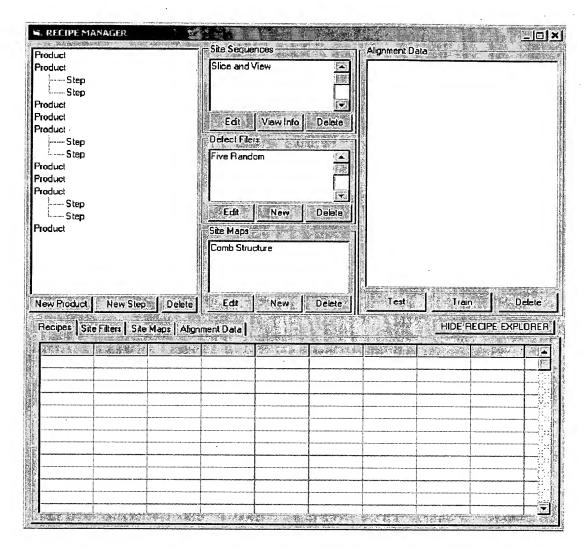


Figure 30



Figure 3P

Control	Description	Behavior
Product	Product/Step Tree View: This is the interface through which specific Steps are created, edited, and deleted.	Sorting: Alphabetized by Product, then by Step.  Node Behavior: Expandable and Collapsible through a standard interface. Persist Expansions for the life of the dialogue.  Scroll Bars: Scrolling should be allowed.
New Product	New Product Button: This is used to add a New Product to the Database.	Click: This should launch a "New Product Wizard" which is described below.
New Step	New Step Button: This is used to add  a New Step to whichever product is selected in the Product/Step Tree View (above).	Enable/Disable: Enable if a Product has been selected. Disabled otherwise.  Click: This should launch the "New Step Wizard" which is described below.
<sup>3</sup> Cama J	Delete Button: This is used to remove products or steps from the database.	Click: This should launch a standard two-button dialogue with the message "Permanently Delete [Product/Step] Information?". The buttons are "Cancel" and "OK".

Figure 3Q

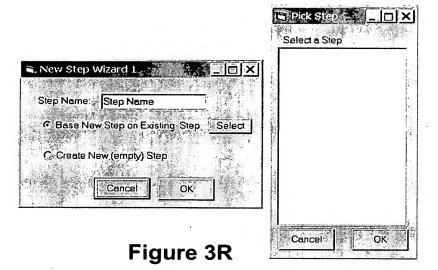




Figure 3S

Control	Description	Behavior
Sice and Ven	Site Sequence List Tree View: This displays a list of Site Sequences which can be	Scrolling: Should be scrollable.  Node Behavior: Expanded nodes
	expanded to show the names of the tools.	should stay expanded.  Alphabetized.
	or the tools.	Click: This should highlight the site sequence.
		Default selection: The first site sequence in the list should be highlighted by default.
		Double-Click: This should expand the node to display the list of tools within the site sequence.
		Mouse Over: This should display the Site Sequence Name followed by the text description of the site sequence (if any).
<u> </u>	Edit Button: This loads the site sequence into the Recipe Builder page.	(Optionally) the page display should be switched to the Recipe Builder.
		Click: Load the selected site sequence into the recipe builder page
Vewleto	View Info Button: THIS BUTTON HAS BEEN REMOVED.	NOT APPLICABLE. (The tree view functionality eliminates the previously envisioned function of this button).
E Delen	Delete Button: This button removes the site sequence from the database.	Click: This removes the site sequence from the database as far as the user is concerned. The actual implementation should include an "Is Deleted" flag to indicate that the site sequence should not be displayed. This will prevent previously configured processes from being invalidated.
Five Random (A)	Site Filter Text Box: This shows a list of all Site Filters available for the selected Product/Step in the Product/Step Tree View control (above).	Alphabetize.  Click: Highlight the site filter.  Default Selection: The first of the list should be highlighted by default.
€ Edi	Edit Button: This is used to edit the highlighted site filter.	Click: Launch the site filter dialog for the highlighted site filter.

Figure 3T



Figure 3U

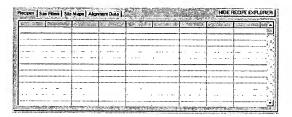


Figure 3X

Control	Description	Behavior
	Alignment Data Tree View. This is a tree view showing the Alignment data in the following order.	Node coloring: The nodes should be colored red if they or a child is untrained.  Data Structure: A preliminary data structure for this tree is shown and described in the following section.
(SC) feet 1.	Test Button. If appropriate, this should test the selected alignment on the wafer loaded into the system.	Enable/Disable: This is dependant on the highlight node of the Alignment Data Tree View. For certain alignments test functionality will not be appropriate and should not, therefore, be applied.  Click: Run the alignment for the highlighted node and all child nodes in the Alignment Data Tree View.
(** Tan <sup>-1</sup> *)	Train Button. If appropriate, this should initiate the portion of the Alignment Training Wizard for the selected node.	Enable/Disable: For some nodes this control may not make sense or may require functionality not provided by the software. In these situations the control should be either disabled or handled through a clear, concise error message. For example, training the zero degree alignments for a wafer loaded at 52 degrees might prompt the user to tilt to zero degrees and try the alignment again.
	*	Click: Run the portion(s) of the alignment training wizard for the highlighted node and child nodes. Note that there may be unanticipated exceptions that need to be dealt with (such as no wafer is loaded) that will require increased robustness in the handling of errors and exceptions. These will be ferreted out at a later time.
Duine /	Delete Button: This permanently deletes alignment data from the database.	Click: This should launch a standard two button dialogue with the message "This will

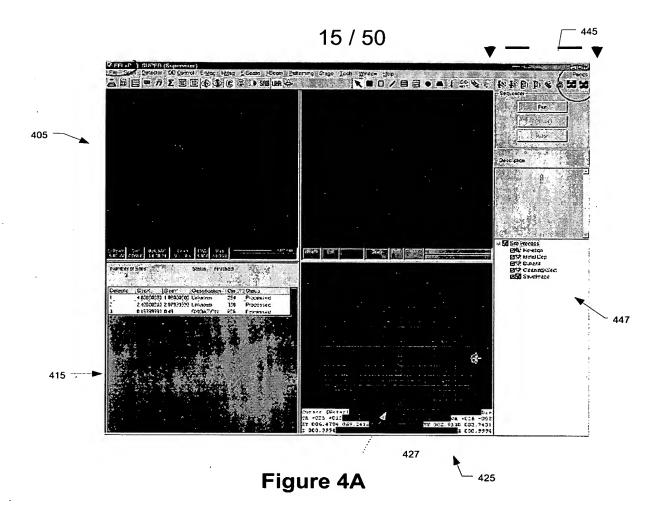
Figure 3V

13 / 30			
Control	Description	Behavior	
(HIDE AFORE EXPLORER)		,	
Porces	Recipe Tab. This should have the following fields.		
	o Product	•	
	o Step		
	o Recipe Name		
	o Creation Date		
[Do Fabre ]	Site Filter Tab. This should have the fields listed below. As an added feature, there could be a "view filter button" to allow a quick look at the data through a new window.		
	o Product		
	o Step		
	o Site Filter Name		
	o Creation Date		
i sa Mera	Site Map Tab. This should have the fields listed below. As an added feature, there could be a "view filter button" to allow a quick look at the data in a new window (similar to above).  O Product O Step O Site Map Name O Creation Date		
Abron O.la	Alignments Tab. This is a complex control, but the should have the fields listed below. Alignment Node should be a path which indicates where the alignment data exists on a tree structure identical to that described above.  O Product		

Figure 3Y

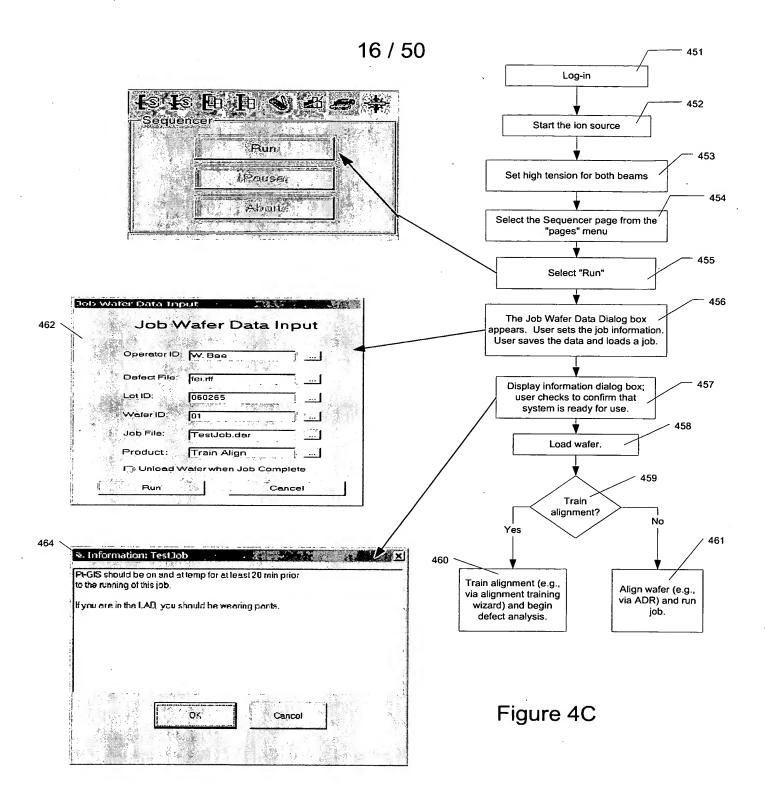
- ❖ Alignment Name #1
  - o Wafer Alignment
    - Product Offset
    - Zero Degrees
      - Alignment Dies
      - Top-Down Electron Beam Image
      - .Ion Beam Image
    - Fifty-Two Degrees
      - Alignment Dies
      - Ion Beam Image
      - Electron Beam Image
  - o System Calibrations
    - Height Probe Offset
      - Zero Degrees
      - Fifty-Two Degrees
- Alignment Name # 2

Figure 3Z



ltem	Description	
Run	oads the wafer and runs the selected job.	
Pause	Pause job execution	
Abort	Terminate job execution	
Description	Comment text describing job if included in job	
Site Process	Displays job process tools	

Figure 4B



Job Wafer Data Imp	ut. S
Job <b>W</b>	/afer Data Input
Operator ID:	W. Bee
Defect File:	fei.rff
Lot ID:	060265
₩afer ID:	01
Job File	TestJob.dar
Product: □ Unioad W	Train Align 'afer when Job Complete
Run	Cancel

Figure 4D

Interface Item	Description
Operator ID	Required field where the user enters name.
Defect File	Defect file for the job. User opens an existing defect file. Clicking the select button opens the Select Defect File dialog box.
Lot ID	Maximum of 15 characters. Value is read in from defect file or job file, selected from dialog box, or entered by the operator.
Wafer ID	Maximum of 5 characters. Value is read in from defect file or job file, selected from dialog box, or entered by the operator.
Job File	Selects a recipe or job file. The recipe contains no wafer information. The job file contains wafer information. They have different extensions, .daj and .dar.
Product	Identifies the alignment wizard for the wafer. If TRAIN ALIGN is selected, when the user clicks RUN, the Alignment Training wizard starts.
Cass A/B	Shows the slots that are occupied.
Inventory	Inventories the cassettes.
FlexiLock	Shows if wafer is in the cassette.
Unload wafer when job complete	Provides automated wafer unloading when a job is complete.
RUN	Dialog box closes and the Information dialog box displays. When user clicks OK in Information dialog box the sequencer runs the job. This button is not active until information for at least one wafer is entered.
Cancel .	Dialog box closes without saving the values. In job builder, the dialog box closes and the Add Tool interface displays. In sequencer, a warning box displays so that the user does not unintentional lose information. Then, the Sequencer page becomes active again.
Select button	Opens dialog where predefined files, wafers, etc., can be selected.

Figure 4E

Job Water Data Inp	out A Sagar James	i Z	*// */	.5380 :50	<b>32</b>	ives!	-A	الد	
Job W	Vafer Data	Input		Cass A-		Coss B	7	nventory	
Operator ID:	W. Bee			2,3		3:			
Defect File:				6.4		3.45			
Lot ID: Water ID:	060265 01			655 655 7 9 7		200			
Job File:	TestJob.dar			117 117					
Product	Train Align	لدر		13 14L		19			
Run		ancel	1	117 18		_16¢ 17 			
		*	-1-	21		19 20 22			
	in the second			23 24 25		24. 25			
		116	***		ـا [لـ	107.34		388	

Figure 4F

Job Wafer Data Imp	ut			
Job W	Vafer Data Input	Coss A-	- Coss B	Inventory
Operator ID:	W. Bee	2.	3	-FlexiLock
Defect Filé:	fei.rft	5 5	4 5 6	
Lot ID:	060265	9	7 8 9	
Job File: Product:	TestJob.dar Train Align	10 12 13	10 12 10	
Plodact	Irrain Aign		14/ 15:3	
Run	Cancel	17 18 19	117	
		22	20	
		24. 25	24 25 T	a de la companya de

Figure 4G

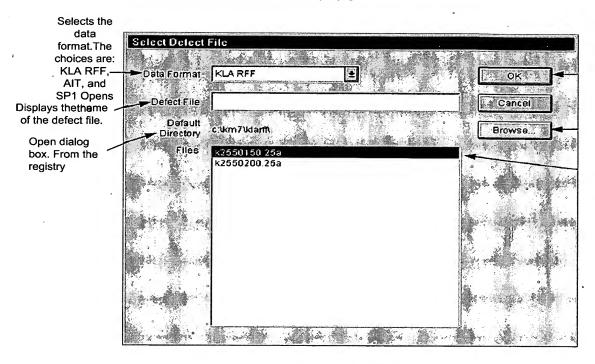


Figure 4H

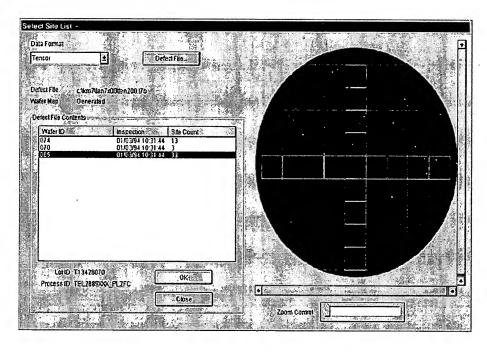


Figure 4I



Figure 4J

Column Header	Description
Wafer ID	The wafer ID as listed in the defect file.
_	The date and time the site list was created during inspection.
Site Count	The number of defect sites in the site list.

Figure 4K

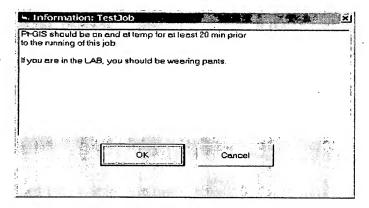


Figure 4L

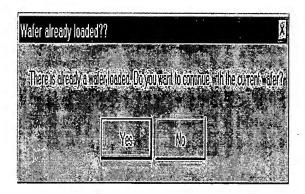


Figure 4M



Figure 4N

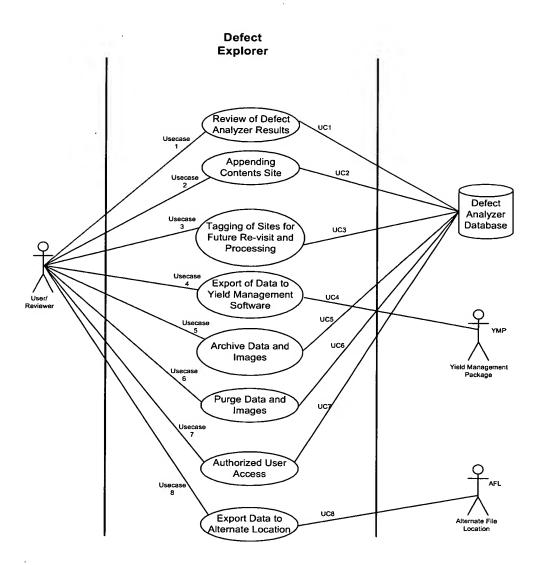


Figure 5

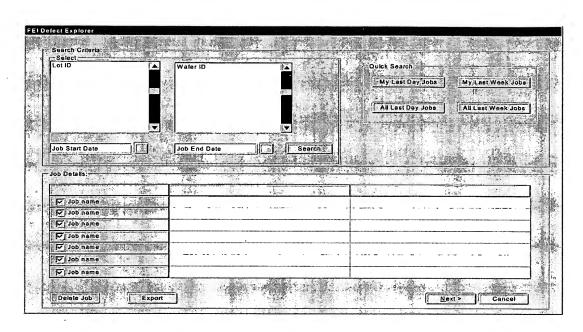


Figure 6A

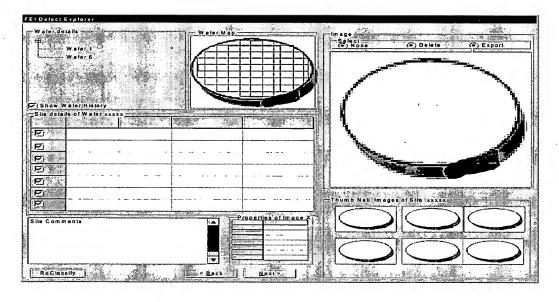


Figure 6B

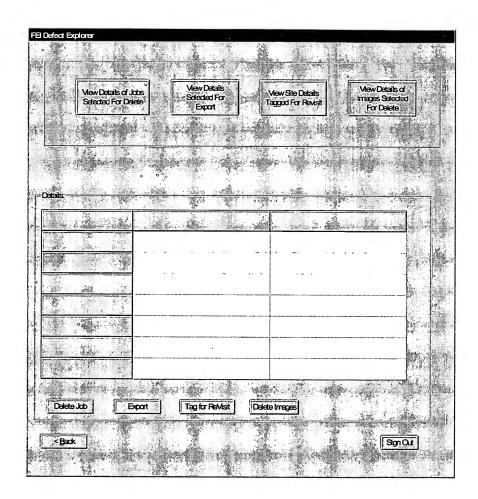


Figure 6C

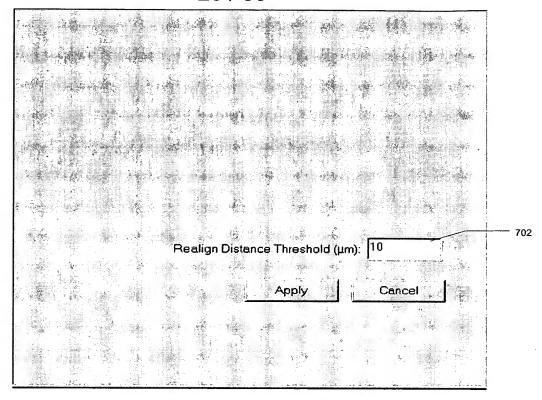


Figure 7A

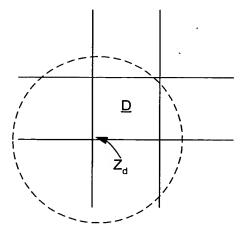
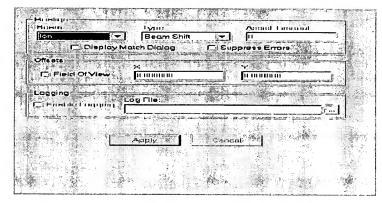


Figure 7B



## Figure 8A

Item	Descrip tion
Realign:	
Beam	Specifies the beam to be used in the alignment.
Туре	Specifies measurement or the type of alignment.
	BEAM SHIFT specifies an alignment using beam shift.
	MEASURE instructs the system to measure the X, Y distance between the center of the
	image and the center of the fiducial mark, in pixels and microns. The result is written to the
	user-specified log file.
	STAGE MOVE specifies an alignment using a stage move.
Assist Timeout	Number of seconds a dialog box remains on screen, prompting for user intervention. If this
	value is 0, no dialog box appears.
Display Match	Displays the Image Match dialog box (see Image Match).
Dialog	
Suppress Errors	When this option is selected, the system ignores image recognition errors. If ENABLE
	LOGGING is selected, image recognition errors are written to the user-specified log file.
Offsets:	
Field of View	Specifies a proportional shift of the field of view.
	When this option is selected, the system shifts the field of view by the proportion of the field
	of view specified in X and Y.
	When this option is not selected, the system shifts the field of view by the distance in microns
	specified in X and Y.
X, Y	Specify the distance by which the system shifts the field of view during alignment.
, .	When FIELD OF VIEW is selected, the values specified in X and Y denote a portion of the
	field of view—e.g., a value of 0.1 equals 10% of the field of view. In one embodiment,
	acceptable values are 0-1.
	When FIELD OF VIEW is not selected, the system shifts the field of view by the distance in
	microns specified in X and Y.
Logging:	
Enable Logging	When this option is selected and a log file is specified, the system logs the following information:
	Name and path of the image file used for realignment
	X location of the fiducial in pixels and microns
	Y location of the fiducial in pixels and microns
	When MEASURE is selected for TYPE, the X, Y distance between the center of the image
	and the center of the fiducial mark, in pixels and microns.
	If the fiducial is not found, the system writes "Fail" to the log file.
Log File	Name and path of the specified log file. Use the adjacent Browse button to navigate to the
	desired directory.
	Figure 8B

Figure 8B

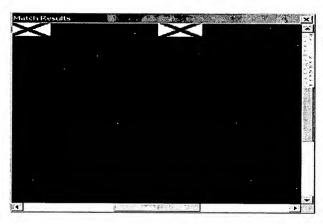


Figure 8C

Cal Align Tool	ALE STATE OF THE S
	realignment failed.
	tton to disable the timer for the
dialog. Center the defect a	nd press OK to manually realign.
Press Retry to retry the	automated alignment Press
CANCEL to	fail the alignment
Realign will fa	ul in: Stop
24 second	- I - I - I - I - I - I - I - I - I - I
	The state of the s
	Retry CANCEL

Figure 8D

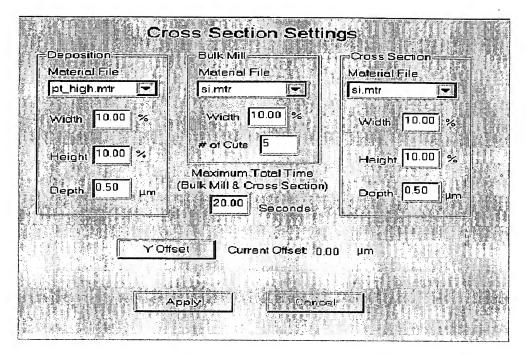
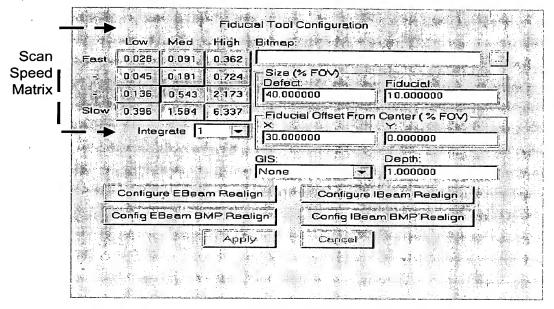


Figure 9A

Item	Descrip tion
Deposition:	
Material File	Displays a dropdown menu for selecting a material file (.mtr). The list contains an entry for every material file available on the system.
Width	Width of the specified cross section (X), as a percentage of the field of view.
H eight	Height of the specified cross section (Y), as a percentage of the field of view. The protective coat will be centered about the location of the cross-section target line.
Depth	Depth of the specified cross section, in microns.
Bulk Mill:	
Number of Cuts	Number of cuts to be made in the bulk mill.
Cross Section:	As in Deposition group, above.
Maximum Total Time	Sets the total pattern time for the bulk mill and cross- section patterning. Defect Analyzer uses this value to select the apertures used for bulk milling and cross- sectioning, based on the specified pattern area, depth, and material file.
Y Offset	Displays a horizontal yellow line in the image quadrant, marking the desired upper boundary of the cross section.  Click anywhere in the field of view to set the location of this yellow line, then click OK in the accompanying dialog box. For further information, see "Setting Y Offset" on page 4-14.

Figure 9B



### Figure 10A

Item	Descrip tion
Scan speed matrix	Sets the frame time and resolution used in ion beam and electron beam images collected after milling of the
	fiducial mark. These images are used for subsequent image recognition.
Integrate	Sets the number of frames to be integrated to allow accumulative noise reduction
Bitmap	Defect Analyzer converts the specified bitmap to a stream file, based on the grayscale levels of individual pixels in the bitmap. Pixels above the median brightness in the
	grayscale are omitted from the stream file; pixels below the median brightness are converted to points.
Size (%FOV)	
Defect	Proportion of the field of view to be occupied by the defect.
Fiducial	Size of the fiducial mark, as a percentage of the field of view.
Fiducial Offset From Center (%FOV)	Sets the offset between the center of the image and the center of the fiducial mark, in X and Y, as a percentage of the field of view.
GIS	Selects the GIS to be used in milling the fiducial. The list contains an entry for every beam chemistry available on the system.
Depth	Depth of the fiducial mark, in microns.
Configure EBeam Realign	
Configure IBeam Realign	
Configure IBeam BMP Realign, Configure EBeam BMP Realign	CONFIGURE EBEAM BMP REALIGN and CONFIGURE IBEAM BMP REALIGN configure the image recognition software for initial matches between a fiducial mark and the bitmap used as the milling pattern.

Figure 10B

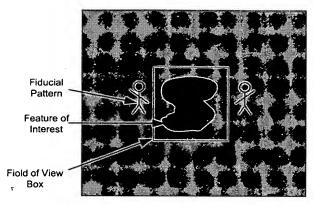


Figure 10C

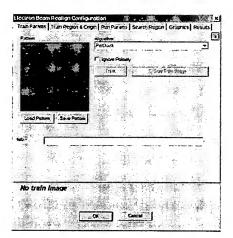


Figure 10E

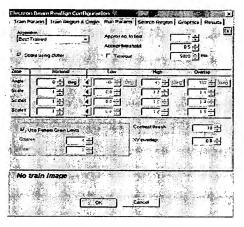


Figure 10G

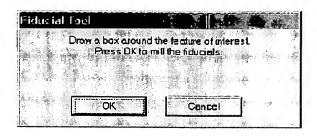


Figure 10D

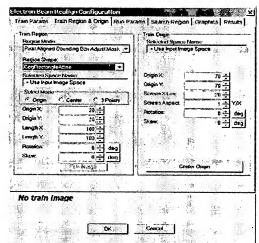


Figure 10F

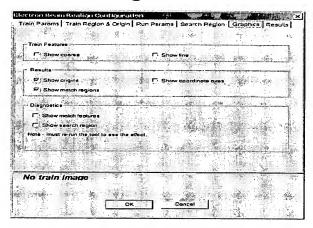


Figure 10H

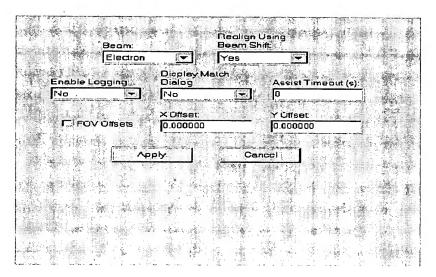


Figure 11A

Item	Descrip tion
Beam	Specifies the beam to be used in the alignment.
Realign Using Beam Shift	Specifies the type of alignment to be made.
	YES specifies an alignment made using beam shift.
_	NO specifies an alignment made using a stage move.
,	For best results, realign the electron beam with stage moves and the
	ion beam with beam shift.
Enable Logging	When this option is selected, the system logs the following information:
	Name and path of the image file used for realignment
	X location of the fiducial in pixels and microns
	Y location of the fiducial in pixels and microns
	If the fiducial is not found, the system writes "Fail" to the log file.
Display Match Dialog	Displays the Image Match dialog box (see "Image Match" on page 4-10).
Assist Timeout(s)	Number of seconds before a dialog box appears, prompting for user
	intervention If this value is 0, no dialog box appears.
FOV Offset	Specifies a proportional shift of the field of view.
	When this option is selected, the system shifts the field of view by
	the proportion of the field of view specified in X and Y.
	When this option is not selected, the system shifts the field of view
	by the distance in microns specified in X and Y.
X Offset, Y Offset	Specify the distance by which the system shifts the field of view
	during alignment.
	When FIELD OF VIEW is selected, the values specified in X and
	Y denote a portion of the field of view—e.g., a value of 0.1 equals
	10% of the field of view. Acceptable values are 0-1.
	When FIELD OF VIEW is not selected, the system shifts the field
	of view by the distance in microns specified in X and Y.

Figur 11B

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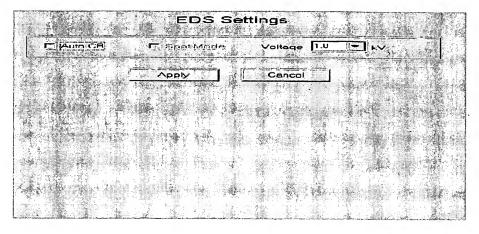


Figure 12A

Item	Descrip tion
Auto CB	Performs automatic contrast and brightness.
Spot Mode	Selects Spot as the scanning mode.
V oltage	V altage to be used to acquire spectrum.

Figure 12B

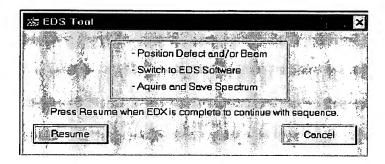


Figure 12C

Interface items Resume	Description Associates the spectrum with the current site and continues automated processing.
Carcel	Does not put anything into the database and gives you the option to fail the site.

Figure 12D

Get System		
©A √ CB CC		
SD CELLICE		
Beam Settings	Detector ☐ Scan Rotation	
Electron Beam	on Beam	
Focus	☐ Focus	
口)Sug 口KV	口 Stig ·	
☐ Spot		A
Electron Beam Shift	☐ Ion Beam Shift	la la
UHR/Search:	[] Megnification	
☐ Contrast/Brightness	Contrast/Brightness	
Apply (	Carcel	

Figure 13A

Item	Descrip tion
Select All/De-Select All	Selects or deselects every option in the Stage, Beam Settings, Electron Beam, and I on Beam groups.
Set Settings Tool Identifier	Identifies a set of stored settings.
Stage	Contains options for recording the positions of the five independent axes.
Beam Settings	Contains options for recording the following current beam settings:
Primary Beam	
Detector	
Scan Rotation	
Electron Beam	Contains options for recording the current electron beam parameters: Focus,
	Stigmation, Accelerating voltage (kV), Spot size, Beam shift, Mode (UHR or Search), Magnification, Contrast/Brightness
Ion Beam	Contains options for recording the current electron beam parameters: Focus,
	Stigmation, Aperture, Beam shift, Magnification, Contrast/Brightnes

Figure 13B

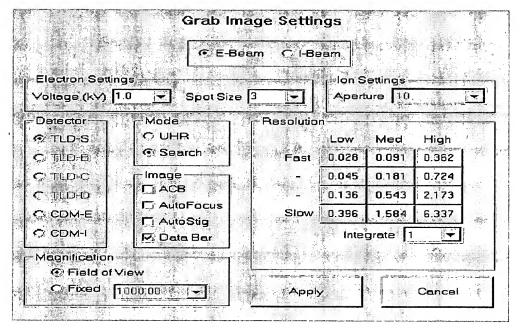


Figure 13C

Item	Descrip tion	
E-Beam	Use electron beam to grab an image.	
I-Beam	Use ion beam to grab an image.	
Electron		
Settings:		
V oltage (kV)	Active only for the electron beam. Specify the accelerating voltage.	
Spot Size	Active only for the electron beam. Specify the spot size.	
Detector	Select the detector used to collect the image. Available selections are dependent on the selected mode and beam. Refer to the xP DualBeam Workstation User's Guide (PN 25417) for information about detector types.	
Mode	Active only for the electron beam. Select Search mode for low magnifications and UHR mode for higher magnifications.	
Image:		
ACB	Automatically adjusts contrast and brightness using the stored values for comparison	
AutoFocus	Automatically corrects the focus, based on the system sharpness criteria.	
AutoStig	Automatically corrects sigmatism, based on the system sharpness criteria. Available for the electron beam.	
Data Bar	Save the databar as seen into the image.	
Magnification	Specifies the magnification used to grab the image. Select either the field-of-view (determined by the Fiducial tool) or choose from a range of preset magnifications.	
Ion Aperture	Active only for the ion beam. Sets the ion aperture.	
Resolution	Selects the scan rate and resolution for grabbing a single frame. The values are those available	
	for Grab Image.	
Integrate	Specifies the number of collected images to be summed to generate the final image.	

Figure 13D

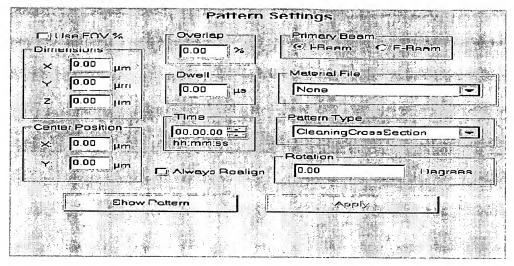


Figure 14A

Item	Descrip tion
Use FOV %	Converts X and Y coordinates in Dimensions and Center Position to a percentage of the field of view
	When this option is selected, X and Y coordinates in
	Dimensions and Center Position denote a
	percentage of the field of view.
	When this option is not selected, X and Y
	coordinates in Dimensions and Center Position are
	in microns.
Dim ensions	Sets the X, Y, and Z pattern dimensions. When
	Pattern Type is set to Circle, X and Y are replaced
	by Rin (inner radius) and Rout (outer radius).
Center Position	Shows the stage X and Y coordinates of the center
	of the pattern relative to the center of the field of
Ossertaria.	view.
Overlap	Beam overlap. Not available when a material file is selected.
Dwell Dwell	Dwell time per pixel. Not available when a material
<b>1</b>	file is selected
Time	Time for milling displayed as either hh:mm:ss or
1	ss:ttt.
Always Realign	When this option is selected, the system always
	realigns to the fiducial mark before milling the
	specified pattern
	When this option is selected, the system only
	realigns to the fiducial mark when an aperture has
Show Pattern/ Remove Pattern	changed or a GIS needle has been inserted.
Show I dieni Kemove Fallein	Displays the currently defined pattern. When a pattern is already on screen, removes that pattern.
Primary Beam	Select I-BEAM or E-BEAM as the beam that will
-	be used for patterning.
Material File	Select the material file for your application. Refer to
į.	the xP DualBeam Workstation User's Guide (PN
	25417) for information about material files.
Pattern Type	Defines the pattern Refer to the xP DualBeam
	Workstation User's Guide (PN 25417) for
	information about available patterns.
Rotation	Rotates the pattern about its center to the specified
	angle.

Figure 14B

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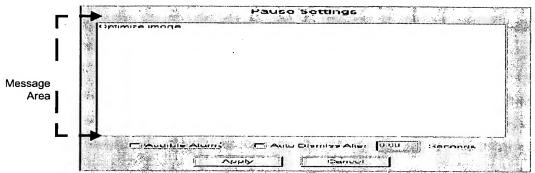
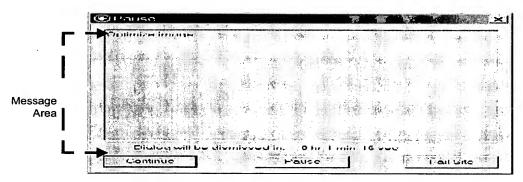


Figure 15A

Item	Descrip tion
Message area	Defines actions the user should take before continuing processing.
Audible alarm	Causes an alarm to sound when the Pause dialog box displays during a job.
Auto dismiss	Selects if the Pause dialog box should time out. Otherwise, the Pause dialog box must be manually dismissed.
	The number of seconds specifies the fixed amount of time Pause dialog box is displayed during a job.

## Figure 15B



## Figure 15C

Item	Descrip tion
Message	Defines action operator should take before proceeding with the process. The text cannot be modified
area	during runtim e.
Timeout	The time the dialog box will be displayed during a job. If the operator does not interact with the tool, the
clock	Pause dialog box times out as specified and the process automatically continues.
Continue	Click to continue processing the current site. The site list grid will show that the site passed
Pause/Res	Stops/restarts the timer. (This button is inactive if AUTO DISMISS was not selected during configuration.)
ume	The process waits for the operator to click either CONTINUE or FAIL.
Fail Site	Click to fail the current site. Further processing at the site is aborted. Processing starts at the next site.
	The site list grid will show that the site failed. If the entire job is to be aborted, the operator can click
	ABORT in the Run Tool Sequence dialog box.

Figure 15D

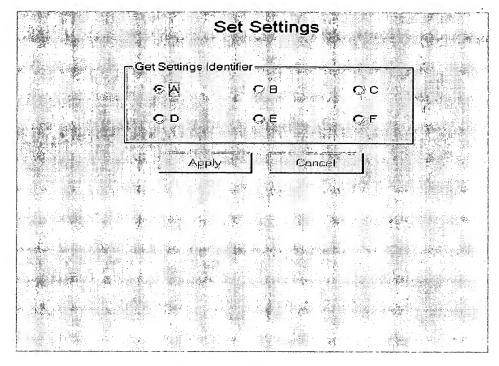


Figure 16

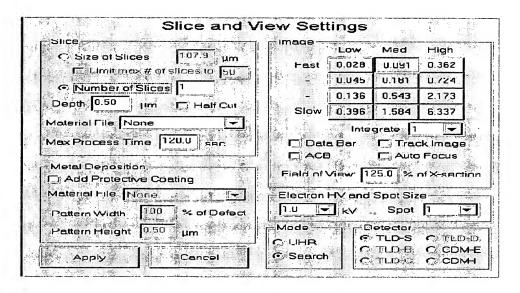


Figure 17A

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Item	Descrip tion	
Slice:	U ser selects either SIZE OF SLICES or NUMBER OF SLICES.	
Size of Slices	Specifies the slice size in microns.	
	The number of slices to be milled will be calculated by dividing the size of the defect	
	(determined by Fiducial tool) by the size of the slices.	
Limit max # of slices to	The maximum number of slices to be made in the Slice and View area.	
Number of Slices	Specifies the number of slices to be milled. The height of each slice is determined by the	
	software dividing the value specified for height (y) by the number of slices. Where is	
	height from?	
	A maximum of 100 individual patterns can be displayed. If the tool calls for more than	
	100 slices, an outline indicating the overall area to be sliced is displayed.	
Depth	Specifies the pattern depth in microns.	
Half Cut	Mills only half way through the defect selected (up to the center cross).	
Material File	Displays a dropdown list for selecting a material file (.mtr). The list contains an entry for	
	every material file available on the system. The default material file is simtr.	
Max Process Time	The maximum time process may occur	
Metal Deposition:		
Add Protective Coating:	If this option is selected, a protective layer will be centered about the Slice and View area.	
3	The scale will be set in the job builder configuration and based upon the size of the slice	
	and view area. If protective coating is not selected, the fields associated with it should be	
	inactive.	
Material File	Displays a dropdown list for selecting a material file (.mtr). The list contains an entry for	
	every material file available on the system. The default material file is either pt_high mtr.	
Pattern Width	Specifies the pattern width, as a percentage of the defect size.	
Pattern Height	Specifies the pattern height, in microns.	
Image:		
Scan Speed Matrix	Sets the frame time and resolution used for the electron beam images of the cross-section	
	face. These values correspond generally to the faster continuous scan rates available in xP.	
	Refer to the xP DualBeam Workstation User's Guide for information about the available resolutions.	
Toda mada		
Integrate	Number of frames to integrate for accumulative noise reduction	
Data Bar	Includes the databar configured in xP in the image.	
ACB	Selects automatically adjusting contrast and brightness, using the stored values for	
Troate Image	comparison  Adjusts the electron beam shift to keep the face of the cross section centered in the field of	
Track Image	view.	
Auto Focus		
Field of View	Initiates autom ated focus before the system begins capturing electron beam images.  Specifies the field of view used for electron beam images of the cross-section face, as a	
rield of view	percentage of the cross-section.	
Electron HV and Spotsize:	kV specifies the electron beam accelerating voltage. Select from the range of voltages	
Electronity and Spoisize.	available for the currently selected imaging mode. SPOTSIZE specifies the actual focused	
	area of the electron beam on the sample.	
Mode	Select UHR or Search as the imaging mode.	
Detector	Select the detector to be used for the electron beam images. Choices are determined by the	
	currently selected imaging mode.	
	various y solocos mugals mose.	

Figure 17B

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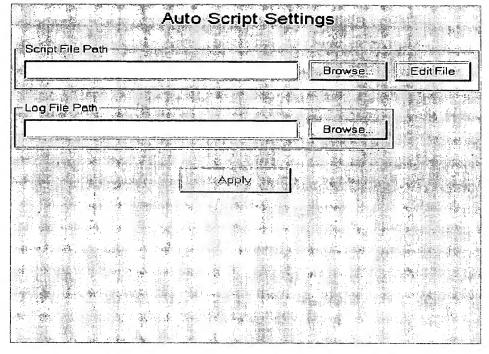


Figure 18A

Item	Descrip tion
Script File Path	Name and path of the AutoScript file.
Browse	Accesses the Open dialog box so you can navigate to a script file.
Edit File	Opens the selected script file in the Windows Notepad® text editor.
Log File Path	Name and path of the log file.
Browse	Accesses the Open dialog box so you can navigate to the log file.

Figure 18B

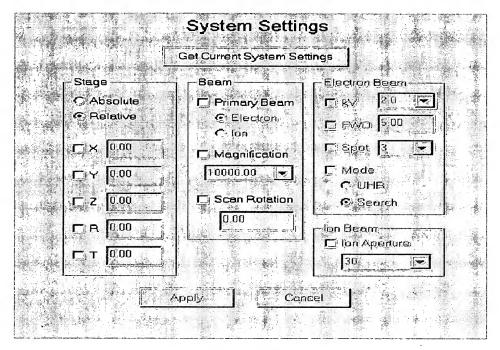


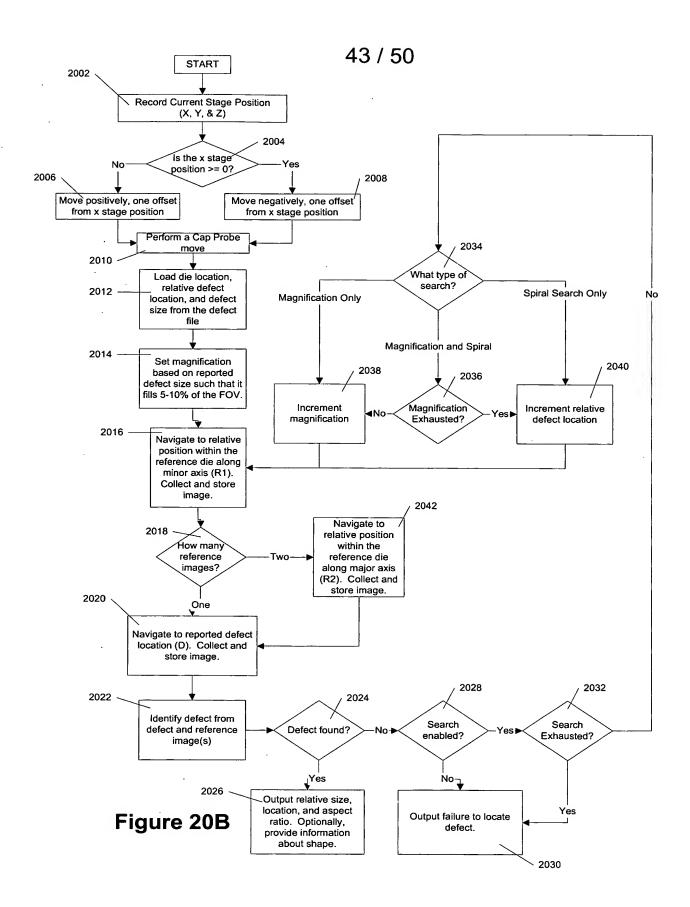
Figure 19A

Item	Descrip tion	
GetCurrentSystem Setting	Getstre our ent settings for all options	
Stage:		
Absolute	Chooses coordinates measured from the certar of the stage.	
Relative	Chooses coordinates messured from the current location on the stage	
X, Y, Z, R, T	Sets the positions of the five independent area	
Beam:		
Primary Beam	Sets the ion beam or electron beam as the primary beam. The selected beam sets the	
	magnification and other image obta of the current image window.	
Magnification	Sets magnification to the speci fied value.	
Scan Rotation	Sets scan rotation to the specified value	
Electron Beam:		
kV	Sets the accelerating voltage for the election beam. Choose a value from the adjecent dropobwn list.	
FWD	Satistive electron beam focus to the firse working distance specified in the adjacent edit box	
Spot	Sets the aperture size for the electron beam. Choose a value from the adjacent dropdown list	
Mode	Selects the mode for the electron beam.	
Ion Beam:		
Ion Aperture	Sets the ion beam current to the aperture (in pA) specified in the adjacent dropdown list.	

Figure 19B

=ADR Parameters Die Offset (x-axis) 5000	DThresh Display:
Center Defect 2 %FOV Text2	Noise Filter:
Probe Eucentric for Reference Im	
. □ use system state	Electron HV and Spot Size
⊙ E-Beam Cl-Beam	
Magnification  O FOV  G Fixed 2500x   ✓	3 ¥
Detector Mode  TLD-S C UHR  Struck Search	Resolution Med - 5.66   ✓ Save Data Bar On Image
CTL-B Integrate CCDM-E CCDM-E	□ AC8 □ AutoFocus
COMP	☐ AutoStig

Figure 20A



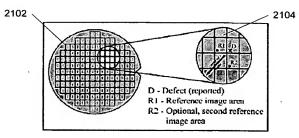
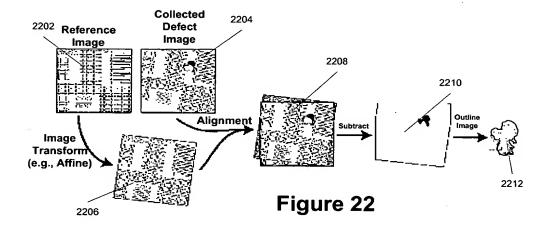


Figure 21



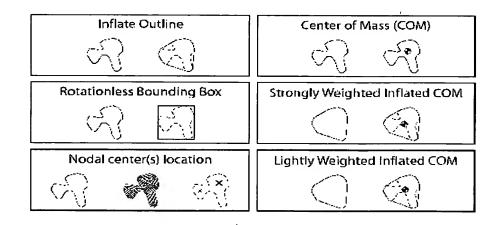
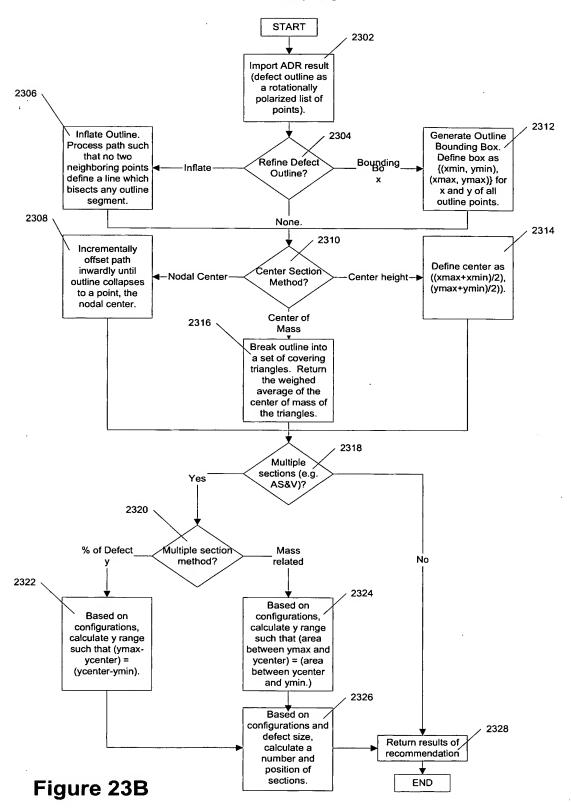
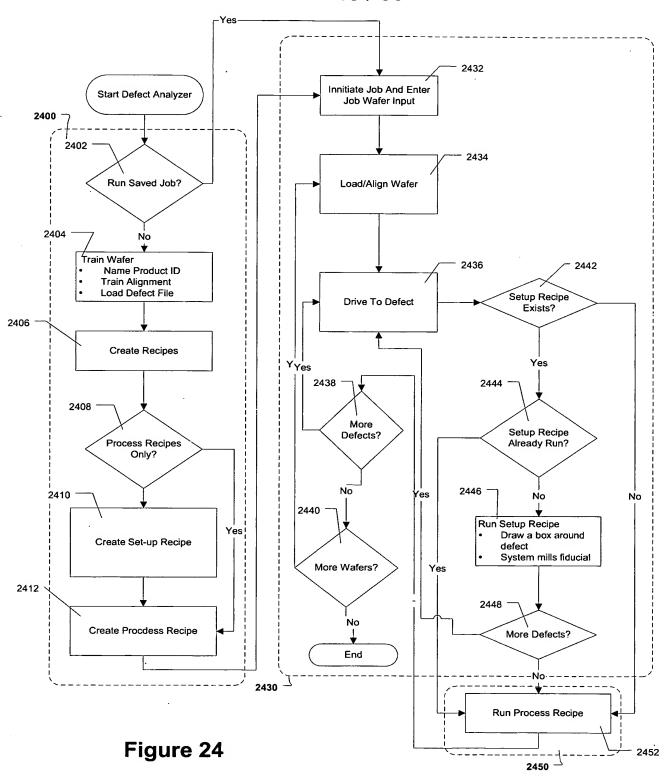


Figure 23A





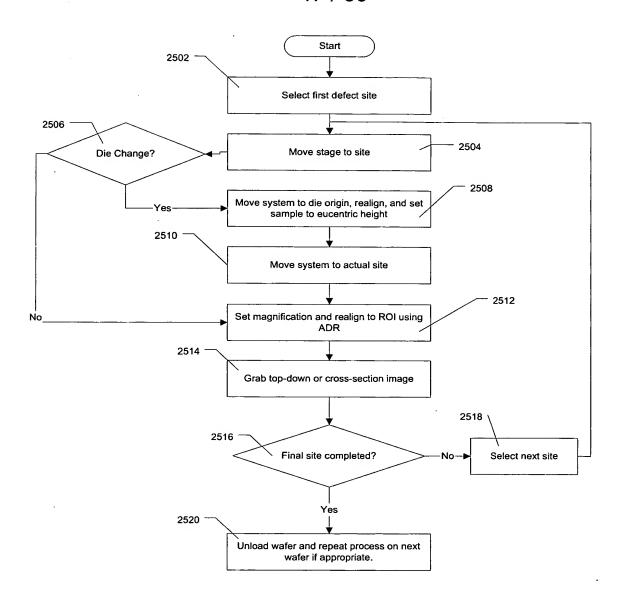


Figure 25

